



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Patent Application Serial No.....10/071,425
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Inventorship Terry L. Gilton et al.
Assignee Micron Technology, Inc.
Group Art Unit 2813
Examiner Thanhha S. Pham
Attorney's Docket No. MI22-1828
Title Semiconductor Processing Method Using Photoresist and an
Antireflective Coating

Commissioner for Patents
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Attention: Official Draftsman

LETTER SUBMITTING FORMAL DRAWINGS

Enclosed are Annotated and Replacement drawing sheets 1 and 3.
Figs. 2 and 9 have been amended.

Figs. 2 and 3 as presented in the application as filed are identical. It is clear from Applicant's application as-filed that Fig. 3 follows processing or is subsequent to the processing of Fig. 2 and that material 18 was intended to be shown as coming into existence of Fig. 3, not in Fig. 2. See, for example Applicant's application as-filed at p. 4, Ins 8, 9, and p. 5, In 18-p.6, In 18. Clearly, there is no reference to photoresist layer 18 in Fig. 2, with such only being introduced with respect to Fig. 3 processing. Accordingly, no new matter is added by fixing this minor oversight in Fig. 2.

In Fig. 9, reference numeral 16 and the lead line extending therefrom have been deleted due to the removal of layer 16 and going from Fig. 8 to

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Fig. 9. Such is clearly supported in Applicant's application as-filed at, for example the last two paragraphs on page 4, and page 9, lines 3-6. Accordingly, no new matter is added.


It is respectfully requested that the drawings as amended herein be entered and acknowledgment of receipt of the formal drawing sheets and their acceptance into the file is requested.

Respectfully submitted,

Dated: _____

9-27-04

By: _____


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Enclosures: Annotated and Replacement Sheets 1 and 3 (Figs. 1-3 and 7-9)